

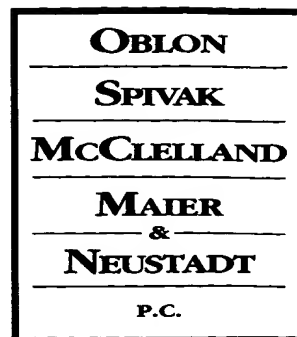
DOCKET NO.: 0039-7632-0X

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APR 18 2001

TC 2000 MAIL ROOM

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231



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Re: Serial No.: 09/531,163  
Applicants: Hiroyuki YANO, et al.  
Filing Date: March 17, 2000  
For: AQUEOUS DISPERSION, AQUEOUS DISPERSION  
FOR CHEMICAL MECHANICAL POLISHING  
USED FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, METHOD FOR  
MANUFACTURE OF SEMICONDUCTOR  
DEVICES, AND METHOD FOR FORMATION OF  
EMBEDDED WIRING

GAU: 2823

Examiner: K. EATON

SIR:

Attached hereto for filing are the following papers:

### RESPONSE TO RESTRICTION REQUIREMENT

Our check in the amount of \$-0- is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. §1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. **15-0030**. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. §1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.



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Step 1  
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APR 17 2001

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

TC 2500 MAIL ROOM

RE APPLICATION OF:

Hiroyuki YANO, et al.

: GROUP ART UNIT: 2823

SERIAL NO.: 09/531,163

:

FILED: March 17, 2000

: EXAMINER: K. EATON

FOR: AQUEOUS DISPERSION, AQUEOUS DISPERSION FOR CHEMICAL  
MECHANICAL POLISHING USED FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, METHOD FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, AND METHOD FOR FORMATION OF  
EMBEDDED WIRING

### RESPONSE TO RESTRICTION REQUIREMENT

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Responsive to the Official Action dated March 20, 2001, Applicants elect, with  
traverse, Group I, Claims 1-39, for further prosecution.

### REMARKS

The Office has required restriction in the present application as follows:

Group I: Claims 1-39, drawn to an aqueous dispersion characterized by containing  
polymer particles; and

Group II: Claims 40-43, drawn to a method for formation of embedded wiring.

Applicants elect, with traverse, Group I, Claims 1-39, for further prosecution.

Restriction is only proper if the claims of the restricted groups are either independent  
or patentably distinct. The burden of proof is on the Office to provide reasons and/or  
examples to support any conclusion with regard to patentable distinctness. MPEP §803.